



Plasma Science and Technology

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Message from the Guest Editor

The objective of this Special Issue of Applied Sciences, entitled “Plasma Science and Technology”, is to summarize in a single issue the major and latest techniques that are used to produce plasma and their applications as well as various scientific studies related to laboratory plasmas. This Special Issue is not limited to plasma physics and chemistry but is open to other scientific fields and to interdisciplinary researchers. Therefore, this Special Issue welcomes original manuscripts concerning plasma diagnostics, plasma physics and plasma chemistry, plasma science, plasma production and technology, and plasma applications. In addition to laboratory plasmas, manuscripts devoted to astrophysical plasmas will also be considered.

Keywords

- plasma physics
- plasma chemistry
- plasma science
- plasma technologies
- low-temperature plasmas
- high-temperature plasmas
- low-density plasmas
- high-density plasmas
- laboratory plasmas
- astrophysical plasmas
- magnetic fusion plasmas
- plasma diagnostics
- plasma applications (medical, industrial, agronomical)





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Message from the Editor-in-Chief

As the world of science becomes ever more specialized, researchers may lose themselves in the deep forest of the ever increasing number of subfields being created. This open access journal Applied Sciences has been started to link these subfields, so researchers can cut through the forest and see the surrounding, or quite distant fields and subfields to help develop his/her own research even further with the aid of this multi-dimensional network.

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